

ABSTRACT

Provided is a substrate with a conductive film for manufacturing a reflective mask which has a rear-surface conductive film with high mechanical strength and is
5 capable of correcting positional deviation of the reflective mask from the rear surface side by a laser beam or the like. A substrate (50) with a conductive film has a conductive film (23) formed on one surface of a main surface of a mask blank substrate (10) used for lithography, wherein the conductive film includes a transparent
conductive layer (23a) provided on a substrate side and an upper layer (23b) provided
10 on the transparent conductive layer, the conductive film has a transmittance of 10% or more for light of wavelength 532 nm, the upper layer is made of a material including tantalum (Ta) and boron (B), and the upper layer has a film thickness of 0.5 nm or more and less than 10 nm.